

ABSTRACT OF THE DISCLOSURE

Provided are a novel halogenoacetoxyadamantane derivative which is useful as a modifying agent for a resin for a photoresist and a dry etching resistance-improving agent in the photolithography field, agricultural and medical intermediates and a compound for other various industrial products and a process for producing the same.

To be specific, provided are a halogenoacetoxyadamantane derivative having a halogenoacetoxy group in an adamantane skeleton and a process for producing a halogenoacetoxyadamantane derivative, comprising the step of reacting a hydroxyl group of an adamantane skeleton with halogenoacetic halide or reacting the above hydroxyl group with a lithiation agent to derive it into a lithiumoxy group and then reacting halogenoacetic halide to introduce a halogenoacetoxy group.